Appln No. 10/791,197 Amdt date September 14, 2006 Reply to Office action of June 15, 2006

## REMARKS/ARGUMENTS

In the Office action dated June 15, 2006, the examiner rejected claims 1-5 under 35 U.S.C. § 103(a) as allegedly obvious over Hirano, et al. (U.S. Patent No. 6,879,107) in view of Ahn (KR 20010463093). In so rejecting, the examiner admits that Hirano fails to disclose the use of Si in the MgO protection layer and relies on Ahn to remedy this deficiency. Applicant respectfully traverses this rejection.

Hirano is directed to minimizing impurities in the MgO protection layer and identifies several metals as such impurities. Column 2, line 66 through column 3, line 2; Column 2, lines 53-59; Column 4, lines 7-12.. In contrast, Ahn discloses a MgO protection layer having at least two added metal oxides selected from oxidized steel, calcium oxide, sodium oxide, potassium oxide, silicon oxide, boron oxide and chrome oxide. Because Hirano is directed to *minimizing* impurities in the MgO protection layer, one of ordinary skill in the art would not be motivated to introduce an *additional* impurity, such as the silicon oxide disclosed in Ahn.

Further, Ahn discloses the use of metal oxides in the MgO protection layer. In contrast, independent claim 1 recites the use of Si and Fe in their elemental forms.

Moreover, as noted in the specification, the discharge delay time of the plasma display device depends on the amount of Fe in the MgO protection layer. See specification, page 3, lines 27-28. Controlling the amount of Fe in the MgO protection layer within the claimed range results in shortened discharge delay times. As shown in Fig. 3 of the present application, when the amount of Fe in the MgO protection layer is outside the claimed range, the discharge delay time is prolonged. While Hirano discloses minimizing impurities such as Fe and other metals, Hirano fails to disclose that Fe is present in the MgO protection layer in an amount within the claimed range. Rather, Hirano appears to disclose that the total amount of impurities (including Fe and several different identified impurities) is 400 ppm or less. Column 4, lines 7-12. Accordingly, independent claim 1 and all claims dependent therefrom, including claims 2-5, are allowable over Hirano and Ahn.

Appln No. 10/791,197 Amdt date September 14, 2006 Reply to Office action of June 15, 2006

Claims 1-5 remain pending in this application and applicant submits that all of pending claims 1-5 are in condition for allowance. Applicant therefore respectfully requests a timely indication of allowance. However, if there are any remaining issues that can be addressed by telephone, applicant invites the examiner to contact applicant's counsel at the number indicated below.

Respectfully submitted,
CHRISTIE, PARKER & HALE, LLP

David A. Plumley

Reg. No. 37,208 626/795-9900

LES/les

LDB PAS700642.1-\*-09/14/06 10:54 AM